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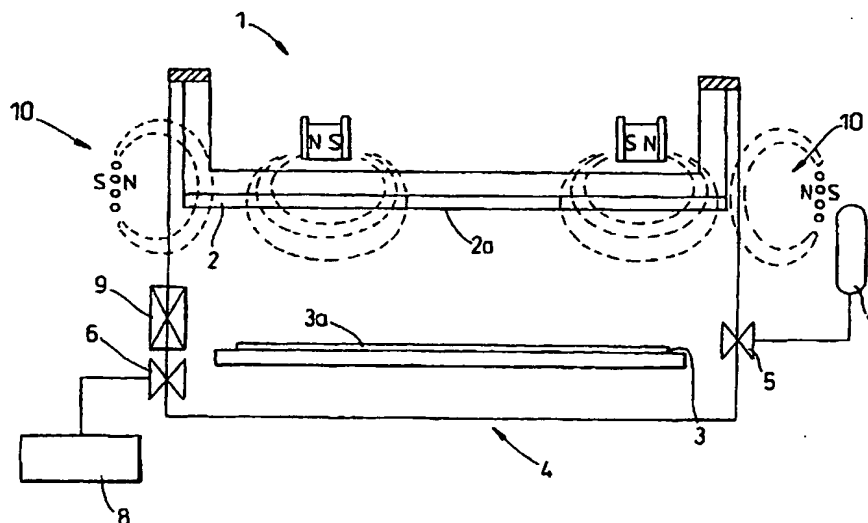
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(54) Abstract Title

**Methods of sputtering using Krypton**

(57) A method of sputtering a layer on a substrate having a plurality of recesses or openings includes using Krypton as a sputtering gas and is characterised in that the gas flow is less than 20 sccm and or the Krypton pressure is less than 1 millitor.



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